

# Kenji Ishikawa

## List of Publications by Year in descending order

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284  
papers

5,486  
citations

125106

35  
h-index

139680

61  
g-index

294  
all docs

294  
docs citations

294  
times ranked

3993  
citing authors

#	ARTICLE	IF	CITATIONS
1	Enhancement of ethanol production and cell growth in budding yeast by direct irradiation of low-temperature plasma. Japanese Journal of Applied Physics, 2022, 61, SA1007.	0.8	1
2	Functional nitrogen science based on plasma processing: quantum devices, photocatalysts and activation of plant defense and immune systems. Japanese Journal of Applied Physics, 2022, 61, SA0805.	0.8	13
3	Perspectives on functional nitrogen science and plasma-based in situ functionalization. Japanese Journal of Applied Physics, 2022, 61, SA0802.	0.8	6
4	Scaffolds with isolated carbon nanowalls promote osteogenic differentiation through Runt-related transcription factor 2 and osteocalcin gene expression of osteoblast-like cells. AIP Advances, 2022, 12, .	0.6	3
5	Plasma-assisted thermal-cyclic atomic-layer etching of tungsten and control of its selectivity to titanium nitride. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2022, 40, 022201.	0.6	1
6	Low-temperature reduction of SnO <sub>2</sub> by floating wire-assisted medium-pressure H <sub>2</sub> /Ar plasma. Plasma Processes and Polymers, 2022, 19, .	1.6	3
7	In-liquid plasma synthesis of iron-nitrogen-doped carbon nanoflakes with high catalytic activity. Plasma Processes and Polymers, 2022, 19, .	1.6	3
8	Cytotoxicity of plasma-irradiated lactate solution produced under atmospheric airtight conditions and generation of the methyl amino group. Applied Physics Express, 2022, 15, 056001.	1.1	6
9	Study of optical emission spectroscopy using modified Boltzmann plot in dual-frequency synchronized pulsed capacitively coupled discharges with DC bias at low-pressure in Ar/O <sub>2</sub> /C <sub>4</sub> F <sub>8</sub> plasma etching process. Physical Chemistry Chemical Physics, 2022, 24, 13883-13896.	1.3	5
10	Wide range applications of process plasma diagnostics using vacuum ultraviolet absorption spectroscopy. Reviews of Modern Plasma Physics, 2022, 6, .	2.2	4
11	Selective etching of SiN against SiO <sub>2</sub> and poly-Si films in hydrofluoroethane chemistry with a mixture of CH <sub>2</sub> FCH <sub>2</sub> , O <sub>2</sub> , and Ar. Applied Surface Science, 2021, 541, 148439.	3.1	17
12	Influences of substrate temperatures on etch rates of PECVD-SiN thin films with a CF <sub>4</sub> /H <sub>2</sub> plasma. Applied Surface Science, 2021, 542, 148550.	3.1	20
13	Improvement of yield and grain quality by periodic cold plasma treatment with rice plants in a paddy field. Plasma Processes and Polymers, 2021, 18, .	1.6	35
14	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. Scientific Reports, 2021, 11, 2539.	1.6	28
15	Growth inhibition effect on Trypanosoma brucei gambiense by the oxidative stress supplied from low-temperature plasma at atmospheric pressure. Japanese Journal of Applied Physics, 2021, 60, 020601.	0.8	0
16	Hydrogen peroxide in lactate solutions irradiated by non-equilibrium atmospheric pressure plasma. Plasma Sources Science and Technology, 2021, 30, 04LT03.	1.3	8
17	Cancer Treatments Using Low-Temperature Plasma. Current Medicinal Chemistry, 2021, 28, 8549-8558.	1.2	12
18	Brain cell proliferation in adult rats after irradiation with nonequilibrium atmospheric pressure plasma. Applied Physics Express, 2021, 14, 067002.	1.1	4

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19	Plasma-activated Ringer's lactate solution inhibits the cellular respiratory system in HeLa cells. <i>Plasma Processes and Polymers</i> , 2021, 18, 2100056.	1.6	9
20	Lysosomal nitric oxide determines transition from autophagy to ferroptosis after exposure to plasma-activated Ringer's lactate. <i>Redox Biology</i> , 2021, 43, 101989.	3.9	55
21	Effects of hydrogen content in films on the etching of LPCVD and PECVD SiN films using CF <sub>4</sub> /H <sub>2</sub> plasma at different substrate temperatures. <i>Plasma Processes and Polymers</i> , 2021, 18, e2100078.	1.6	7
22	Novel Method of Rebound Tailing Pulse (RTP) for Water Dissociation. <i>IEEE Transactions on Plasma Science</i> , 2021, 49, 2893-2900.	0.6	1
23	Low temperature plasma irradiation products of sodium lactate solution that induce cell death on U251SP glioblastoma cells were identified. <i>Scientific Reports</i> , 2021, 11, 18488.	1.6	20
24	Effects of Carbon Nanowalls (CNWs) Substrates on Soft Ionization of Low-Molecular-Weight Organic Compounds in Surface-Assisted Laser Desorption/Ionization Mass Spectrometry (SALDI-MS). <i>Nanomaterials</i> , 2021, 11, 262.	1.9	7
25	Inactivation mechanism of fungal spores through oxygen radicals in atmospheric-pressure plasma. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010503.	0.8	8
26	Insights into normothermic treatment with direct irradiation of atmospheric pressure plasma for biological applications. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010502.	0.8	10
27	Reduction in photon-induced interface defects by optimal pulse repetition rate in the pulse-modulated inductively coupled plasma. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 010906.	0.8	2
28	On the Etching Mechanism of Highly Hydrogenated SiN Films by CF <sub>4</sub> /D <sub>2</sub> Plasma: Comparison with CF <sub>4</sub> /H <sub>2</sub> . <i>Coatings</i> , 2021, 11, 1535.	1.2	7
29	in-Liquid Plasma Synthesis of Nanographene with a Mixture of Methanol and 1-Butanol. <i>ChemNanoMat</i> , 2020, 6, 604-609.	1.5	4
30	Gas-phase and film analysis of hydrogenated amorphous carbon films: Effect of ion bombardment energy flux on sp <sup>2</sup> carbon structures. <i>Diamond and Related Materials</i> , 2020, 104, 107651.	1.8	5
31	<i>in situ</i> surface analysis of an ion-energy-dependent chlorination layer on GaN during cyclic etching using Ar <sup>+</sup> ions and Cl radicals. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	0.9	13
32	Reaction science of layer-by-layer thinning of graphene with oxygen neutrals at room temperature. <i>Carbon</i> , 2020, 170, 93-99.	5.4	5
33	Formation of spherical Sn particles by reducing SnO <sub>2</sub> film in floating wire-assisted H <sub>2</sub> /Ar plasma at atmospheric pressure. <i>Scientific Reports</i> , 2020, 10, 17770.	1.6	7
34	Small size gold nanoparticles enhance apoptosis-induced by cold atmospheric plasma via depletion of intracellular GSH and modification of oxidative stress. <i>Cell Death Discovery</i> , 2020, 6, 83.	2.0	46
35	Plasma Agriculture from Laboratory to Farm: A Review. <i>Processes</i> , 2020, 8, 1002.	1.3	125
36	Influence of chamber pressure on the crystal quality of homo-epitaxial GaN grown by radical-enhanced MOCVD (REMOCVD). <i>Journal of Crystal Growth</i> , 2020, 549, 125863.	0.7	4

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37	Non-thermal plasma-activated lactate solution kills U251SP glioblastoma cells in an innate reductive manner with altered metabolism. Archives of Biochemistry and Biophysics, 2020, 688, 108414.	1.4	20
38	Numerical simulations of stable, high-electron-density atmospheric pressure argon plasma under pin-to-plane electrode geometry: effects of applied voltage polarity. Journal Physics D: Applied Physics, 2020, 53, 265204.	1.3	23
39	Electronic properties and primary dissociation channels of fluoromethane compounds. Japanese Journal of Applied Physics, 2020, 59, SJJE02.	0.8	6
40	Steering of surface discharges on through-glass-vias combined with high-density nonequilibrium atmospheric pressure plasma generation. Journal Physics D: Applied Physics, 2020, 53, 435203.	1.3	1
41	Adjusted multiple gases in the plasma flow induce differential antitumor potentials of plasma-activated solutions. Plasma Processes and Polymers, 2020, 17, 1900259.	1.6	17
42	Interaction of oxygen with polystyrene and polyethylene polymer films: A mechanistic study. Journal of Applied Physics, 2020, 127, .	1.1	20
43	Synthesis of isolated carbon nanowalls via high-voltage nanosecond pulses in conjunction with CH <sub>4</sub> /H <sub>2</sub> plasma enhanced chemical vapor deposition. Carbon, 2020, 161, 403-412.	5.4	21
44	Electron spin resonance as a tool to monitor the influence of novel processing technologies on food properties. Trends in Food Science and Technology, 2020, 100, 77-87.	7.8	37
45	Roles of Atomic Nitrogen/Hydrogen in GaN Film Growth by Chemically Assisted Sputtering with Dual Plasma Sources. ACS Omega, 2020, 5, 26776-26785.	1.6	2
46	Characterization of a microsecond pulsed non-equilibrium atmospheric pressure Ar plasma using laser scattering and optical emission spectroscopy. Plasma Science and Technology, 2020, 22, 065404.	0.7	1
47	In-plane modification of hexagonal boron nitride particles via plasma in solution. Applied Physics Express, 2020, 13, 066001.	1.1	7
48	Etching characteristics of PECVD-prepared SiN films with CF <sub>4</sub> /D <sub>2</sub> and CF <sub>4</sub> /H <sub>2</sub> plasmas at different temperatures. , 2020, , .		1
49	Numerical analysis of coaxial dielectric barrier helium discharges: three-stage mode transitions and internal bullet propagation. Applied Physics Express, 2020, 13, 086001.	1.1	6
50	Laser-induced-plasma-activated medium enables killing of HeLa cells. Applied Physics Express, 2020, 13, 106001.	1.1	0
51	Progress and perspectives in dry processes for emerging multidisciplinary applications: how can we improve our use of dry processes?. Japanese Journal of Applied Physics, 2019, 58, SE0803.	0.8	4
52	Atmospheric Pressure Plasma-Treated Carbon Nanowallsâ€™ Surface-Assisted Laser Desorption/Ionization Time-of-Flight Mass Spectrometry (CNW-SALDI-MS). Journal of Carbon Research, 2019, 5, 40.	1.4	5
53	Rapid thermal-cyclic atomic-layer etching of titanium nitride in CHF <sub>3</sub> /O <sub>2</sub> downstream plasma. Journal Physics D: Applied Physics, 2019, 52, 475106.	1.3	12
54	Self-limiting reactions of ammonium salt in CHF <sub>3</sub> /O <sub>2</sub> downstream plasma for thermal-cyclic atomic layer etching of silicon nitride. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	24

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55	Oxidative stress-dependent and -independent death of glioblastoma cells induced by non-thermal plasma-exposed solutions. <i>Scientific Reports</i> , 2019, 9, 13657.	1.6	48
56	Electrochemical Reaction in Hydrogen Peroxide and Structural Change of Platinum Nanoparticle-Supported Carbon Nanowalls Grown Using Plasma-Enhanced Chemical Vapor Deposition. <i>Journal of Carbon Research</i> , 2019, 5, 7.	1.4	3
57	Facile synthesis of SnO <sub>2</sub> -graphene composites employing nonthermal plasma and SnO <sub>2</sub> nanoparticles-dispersed ethanol. <i>Journal Physics D: Applied Physics</i> , 2019, 52, 175301.	1.3	8
58	Modifications of surface and bulk properties of magnetron-sputtered carbon films employing a post-treatment of atmospheric pressure plasma. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SAAC07.	0.8	4
59	Simultaneous achievement of antimicrobial property and plant growth promotion using plasma-activated benzoic compound solution. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900023.	1.6	19
60	Progress and perspectives in dry processes for leading-edge manufacturing of devices: toward intelligent processes and virtual product development. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0804.	0.8	7
61	Review of methods for the mitigation of plasma-induced damage to low dielectric constant interlayer dielectrics used for semiconductor logic device interconnects. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900039.	1.6	13
62	Rethinking surface reactions in nanoscale dry processes toward atomic precision and beyond: a physics and chemistry perspective. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0801.	0.8	9
63	Progress and perspectives in dry processes for nanoscale feature fabrication: fine pattern transfer and high-aspect-ratio feature formation. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0802.	0.8	24
64	Electronic properties and primary dissociation channels of fluoroethane compounds. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SEEF01.	0.8	5
65	Gene Expression of Osteoblast-like Cells on Carbon-Nanowall as Scaffolds during Incubation with Electrical Stimulation. <i>ACS Applied Bio Materials</i> , 2019, 2, 2698-2702.	2.3	6
66	Hetero-epitaxial growth of a GaN film by the combination of magnetron sputtering with Ar/Cl <sub>2</sub> gas mixtures and a separate supply of nitrogen precursors from a high density radical source. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SAAF04.	0.8	2
67	Chemical bonding structure in porous SiOC films ( $\epsilon \sim 2.4$ ) with high plasma-induced damage resistance. <i>Micro and Nano Engineering</i> , 2019, 3, 1-6.	1.4	6
68	Laser-drilling formation of through-glass-via (TGV) on polymer-laminated glass. <i>Journal of Materials Science: Materials in Electronics</i> , 2019, 30, 10183-10190.	1.1	11
69	Plasma-activated solution alters the morphological dynamics of supported lipid bilayers observed by high-speed atomic force microscopy. <i>Applied Physics Express</i> , 2019, 12, 066001.	1.1	3
70	Effects of Ion Bombardment Energy Flux on Chemical Compositions and Structures of Hydrogenated Amorphous Carbon Films Grown by a Radical-Injection Plasma-Enhanced Chemical Vapor Deposition. <i>Journal of Carbon Research</i> , 2019, 5, 8.	1.4	1
71	Effects of BCl <sub>3</sub> addition to Cl <sub>2</sub> gas on etching characteristics of GaN at high temperature. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019, 37, 021209.	0.6	7
72	Effects of plasma shield plate design on epitaxial GaN films grown for large-sized wafers in radical-enhanced metalorganic chemical vapor deposition. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019, 37, 031201.	0.6	4

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73	Adhesion enhancement and amine reduction using film redeposited at the interface of a stack of plasma-enhanced CVD dielectrics for Cu/low- <i>k</i> interconnects. Japanese Journal of Applied Physics, 2019, 58, 020908.	0.8	2
74	Effect of electrical stimulation on proliferation and bone-formation by osteoblast-like cells cultured on carbon nanowalls scaffolds. Applied Physics Express, 2019, 12, 025006.	1.1	8
75	Polyethylene terephthalate (PET) surface modification by VUV and neutral active species in remote oxygen or hydrogen plasmas. Plasma Processes and Polymers, 2019, 16, 1800175.	1.6	26
76	Narrow free-standing features fabricated by top-down self-limited trimming of organic materials using precisely temperature-controlled plasma etching system. Japanese Journal of Applied Physics, 2019, 58, 020906.	0.8	4
77	Single-Step, Low-Temperature Simultaneous Formations and in Situ Binding of Tin Oxide Nanoparticles to Graphene Nanosheets by In-Liquid Plasma for Potential Applications in Gas Sensing and Lithium-Ion Batteries. ACS Applied Nano Materials, 2019, 2, 649-654.	2.4	8
78	Remotely floating wire-assisted generation of high-density atmospheric pressure plasma and SF <sub>6</sub> -added plasma etching of quartz glass. Journal of Applied Physics, 2019, 125, 063304.	1.1	6
79	Simulation-aided design of very-high-frequency excited nitrogen plasma confinement using a shield plate. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2019, 37, .	0.6	2
80	Effects of 3D structure on electrochemical oxygen reduction characteristics of Pt-nanoparticle-supported carbon nanowalls. Journal Physics D: Applied Physics, 2019, 52, 105503.	1.3	5
81	Control of sp <sup>2</sup> -C cluster incorporation of amorphous carbon films grown by H-radical-injection CH <sub>4</sub> /H <sub>2</sub> plasma-enhanced chemical vapor deposition. Japanese Journal of Applied Physics, 2019, 58, 030912.	0.8	8
82	Systematic diagnostics of the electrical, optical, and physicochemical characteristics of low-temperature atmospheric-pressure helium plasma sources. Journal Physics D: Applied Physics, 2019, 52, 165202.	1.3	21
83	Non-thermal plasma-activated medium modified metabolomic profiles in the glycolysis of U251SP glioblastoma. Archives of Biochemistry and Biophysics, 2019, 662, 83-92.	1.4	33
84	Pt nanoparticle-supported carbon nanowalls electrode with improved durability for fuel cell applications using C <sub>2</sub> F <sub>6</sub> /H <sub>2</sub> plasma-enhanced chemical vapor deposition. Applied Physics Express, 2019, 12, 015001.	1.1	6
85	Liquid dynamics in response to an impinging low-temperature plasma jet. Journal Physics D: Applied Physics, 2019, 52, 075203.	1.3	15
86	A 65-nm CMOS Fully Integrated Analysis Platform Using an On-Chip Vector Network Analyzer and a Transmission-Line-Based Detection Window for Analyzing Circulating Tumor Cell and Exosome. IEEE Transactions on Biomedical Circuits and Systems, 2019, 13, 470-479.	2.7	13
87	Oxygen reduction reaction properties of nitrogen-incorporated nanographenes synthesized using in-liquid plasma from mixture of ethanol and iron phthalocyanine. Japanese Journal of Applied Physics, 2018, 57, 040303.	0.8	6
88	Cytotoxicity of cancer HeLa cells sensitivity to normal MCF10A cells in cultivations with cell culture medium treated by microwave-excited atmospheric pressure plasmas. Journal Physics D: Applied Physics, 2018, 51, 115401.	1.3	6
89	Reduced HeLa cell viability in methionine-containing cell culture medium irradiated with microwave-excited atmospheric pressure plasma. Plasma Processes and Polymers, 2018, 15, 1700200.	1.6	12
90	Facile fabrication of a poly(ethylene terephthalate) membrane filter with precise arrangement of through-holes. Japanese Journal of Applied Physics, 2018, 57, 037001.	0.8	3

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91	Nanographene synthesis employing in-liquid plasmas with alcohols or hydrocarbons. Japanese Journal of Applied Physics, 2018, 57, 026201.	0.8	18
92	Electron impact ionization of perfluoro-methyl-vinyl-ether C <sub>3</sub> F <sub>6</sub> O. Plasma Sources Science and Technology, 2018, 27, 015009.	1.3	10
93	Free radical generation by non-equilibrium atmospheric pressure plasma in alcohol-water mixtures: an EPR-spin trapping study. Journal Physics D: Applied Physics, 2018, 51, 095202.	1.3	17
94	Rapid growth of micron-sized graphene flakes using in-liquid plasma employing iron phthalocyanine-added ethanol. Applied Physics Express, 2018, 11, 015102.	1.1	16
95	Nanographene synthesized in triple-phase plasmas as a highly durable support of catalysts for polymer electrolyte fuel cells. Japanese Journal of Applied Physics, 2018, 57, 045101.	0.8	11
96	Plasma-activated medium (PAM) kills human cancer-initiating cells. Pathology International, 2018, 68, 23-30.	0.6	50
97	Selective production of reactive oxygen and nitrogen species in the plasma-treated water by using a nonthermal high-frequency plasma jet. Japanese Journal of Applied Physics, 2018, 57, 0102B4.	0.8	22
98	Glioblastoma Cell Lines Display Different Sensitivities to Plasma-Activated Medium. IEEE Transactions on Radiation and Plasma Medical Sciences, 2018, 2, 99-102.	2.7	3
99	Dissociative properties of 1,1,1,2-tetrafluoroethane obtained by computational chemistry. Japanese Journal of Applied Physics, 2018, 57, 06JC02.	0.8	8
100	Real-time control of a wafer temperature for uniform plasma process. , 2018, , .		1
101	Temperature dependence on plasma-induced damage and chemical reactions in GaN etching processes using chlorine plasma. Japanese Journal of Applied Physics, 2018, 57, 06JD01.	0.8	3
102	Cell Deposition Microchip with Micropipette Control over Liquid Interface Motion. Cell Medicine, 2018, 10, 215517901773315.	5.0	1
103	Impact of helium pressure in arc plasma synthesis on crystallinity of single-walled carbon nanotubes. Japanese Journal of Applied Physics, 2018, 57, 06JF01.	0.8	0
104	Effects of gas residence time of CH <sub>4</sub> /H <sub>2</sub> on sp <sup>2</sup> fraction of amorphous carbon films and dissociated methyl density during radical-injection plasma-enhanced chemical vapor deposition. Japanese Journal of Applied Physics, 2018, 57, 06JE03.	0.8	7
105	Effect of N <sub>2</sub> /H <sub>2</sub> plasma on GaN substrate cleaning for homoepitaxial GaN growth by radical-enhanced metalorganic chemical vapor deposition (REMOCVD). AIP Advances, 2018, 8, 115116.	0.6	4
106	Molecular mechanisms of non-thermal plasma-induced effects in cancer cells. Biological Chemistry, 2018, 400, 87-91.	1.2	43
107	Reaction mechanisms between chlorine plasma and a spin-on-type polymer mask for high-temperature plasma etching. Japanese Journal of Applied Physics, 2018, 57, 106502.	0.8	1
108	Progress in nanoscale dry processes for fabrication of high-aspect-ratio features: How can we control critical dimension uniformity at the bottom?. Japanese Journal of Applied Physics, 2018, 57, 06JA01.	0.8	57

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109	Elevated-temperature etching of gallium nitride (GaN) in dual-frequency capacitively coupled plasma of CH <sub>4</sub> /H <sub>2</sub> at 300–500 °C. <i>Vacuum</i> , 2018, 156, 219-223.	1.6	6
110	Cytotoxic effects of plasma-irradiated fullerene. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 375401.	1.3	1
111	Low-autofluorescence fluoropolymer membrane filters for cell filtration. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 06JF03.	0.8	5
112	New Hopes for Plasma-Based Cancer Treatment. <i>Plasma</i> , 2018, 1, 150-155.	0.7	35
113	Isotropic atomic level etching of tungsten using formation and desorption of tungsten fluoride. , 2018, , .		3
114	Investigation of effects of ion energies on both plasma-induced damage and surface morphologies and optimization of high-temperature Cl <sub>2</sub> plasma etching of GaN. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 026502.	0.8	13
115	Behavior of absolute densities of atomic oxygen in the gas phase near an object surface in an AC-excited atmospheric pressure He plasma jet. <i>Applied Physics Express</i> , 2017, 10, 036201.	1.1	8
116	Spatial profiles of interelectrode electron density in direct current superposed dual-frequency capacitively coupled plasmas. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 155201.	1.3	12
117	Effects of •OH and •NO radicals in the aqueous phase on H <sub>2</sub> O <sub>2</sub> and %ext{NO}_2 generated in plasma-activated medium. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 155202.	1.3	73
118	Characteristics of optical emissions of arc plasma processing for high-rate synthesis of highly crystalline single-walled carbon nanotubes. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 035101.	0.8	5
119	Bactericidal pathway of <i>Escherichia coli</i> in buffered saline treated with oxygen radicals. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 155208.	1.3	24
120	Selective atomic-level etching using two heating procedures, infrared irradiation and ion bombardment, for next-generation semiconductor device manufacturing. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 194001.	1.3	17
121	Intracellular-molecular changes in plasma-irradiated budding yeast cells studied using multiplex coherent anti-Stokes Raman scattering microscopy. <i>Physical Chemistry Chemical Physics</i> , 2017, 19, 13438-13442.	1.3	7
122	Temperature dependence of protection layer formation on organic trench sidewall in H <sub>2</sub> /N <sub>2</sub> plasma etching with control of substrate temperature. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 076202.	0.8	4
123	Progress and prospects in nanoscale dry processes: How can we control atomic layer reactions?. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HA02.	0.8	36
124	Hydrogen peroxide sensor based on carbon nanowalls grown by plasma-enhanced chemical vapor deposition. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 06HF03.	0.8	28
125	Spatial distributions of O, N, NO, OH and vacuum ultraviolet light along gas flow direction in an AC-excited atmospheric pressure Ar plasma jet generated in open air. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 195202.	1.3	37
126	(Invited) Thermal Cyclic Atomic-Level Etching of Nitride Films: A Novel Way for Atomic-Scale Nanofabrication. <i>ECS Transactions</i> , 2017, 80, 3-14.	0.3	5



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127	Thermally enhanced formation of photon-induced damage on GaN films in Cl <sub>2</sub> plasma. Japanese Journal of Applied Physics, 2017, 56, 096501.	0.8	4
128	Cold atmospheric helium plasma causes synergistic enhancement in cell death with hyperthermia and an additive enhancement with radiation. Scientific Reports, 2017, 7, 11659.	1.6	31
129	Absolute density of precursor SiH <sub>3</sub> radicals and H atoms in H <sub>2</sub> -diluted SiH <sub>4</sub> gas plasma for deposition of microcrystalline silicon films. Applied Physics Letters, 2017, 110, 043902.	1.5	4
130	Intracellular responses to reactive oxygen and nitrogen species, and lipid peroxidation in apoptotic cells cultivated in plasma-activated medium. Plasma Processes and Polymers, 2017, 14, 1700123.	1.6	23
131	High-durability catalytic electrode composed of Pt nanoparticle-supported carbon nanowalls synthesized by radical-injection plasma-enhanced chemical vapor deposition. Journal Physics D: Applied Physics, 2017, 50, 40LT01.	1.3	12
132	Growth of InN films by radical-enhanced metal organic chemical vapor deposition at a low temperature of 200 Å°C. Japanese Journal of Applied Physics, 2017, 56, 06HE08.	0.8	4
133	Lipid droplets exhaustion with caspases activation in HeLa cells cultured in plasma-activated medium observed by multiplex coherent anti-Stokes Raman scattering microscopy. Biointerphases, 2017, 12, 031006.	0.6	10
134	Dynamic analysis of reactive oxygen nitrogen species in plasma-activated culture medium by UV absorption spectroscopy. Journal of Applied Physics, 2017, 122, .	1.1	17
135	Crystallization of calcium oxalate dihydrate in a buffered calcium-containing glucose solution by irradiation with non-equilibrium atmospheric pressure plasma. Journal of Applied Physics, 2017, 122, 143301.	1.1	4
136	Surface roughening of photoresist after change of the photon/radical and ion treatment sequence. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 060606.	0.9	2
137	Dependence of absolute photon flux on infrared absorbance alteration and surface roughness on photoresist polymers irradiated with vacuum ultraviolet photons emitted from HBr plasma. Japanese Journal of Applied Physics, 2017, 56, 126503.	0.8	2
138	State of the art in medical applications using non-thermal atmospheric pressure plasma. Reviews of Modern Plasma Physics, 2017, 1, 1.	2.2	90
139	Electron behaviors in afterglow of synchronized dc-imposed pulsed fluorocarbon-based plasmas. Japanese Journal of Applied Physics, 2017, 56, 06HC03.	0.8	10
140	Reduction of chlorine radical chemical etching of GaN under simultaneous plasma-emitted photon irradiation. Applied Physics Express, 2017, 10, 086502.	1.1	3
141	Time Evolution Of Reactive Oxygen Nitrogen Species in Plasma-Activated Essential Media and Water. , 2017, , .		0
142	Plasmatreatment induces blood clot formation; protein aggregation and hemolysis. , 2016, , .		0
143	Plasma Diagnostics. , 2016, , 117-141.		9
144	Effects of Radical Species on Structural and Electronic Properties of Amorphous Carbon Films Deposited by Radical-Injection Plasma-Enhanced Chemical Vapor Deposition. Plasma Processes and Polymers, 2016, 13, 730-736.	1.6	10

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145	Cold plasma interactions with enzymes in foods and model systems. Trends in Food Science and Technology, 2016, 55, 39-47.	7.8	275
146	Real-time temperature monitoring of Si substrate during plasma processing and its heat-flux analysis. Japanese Journal of Applied Physics, 2016, 55, 01AB04.	0.8	6
147	Formation of a SiOF reaction intermixing layer on SiO <sub>2</sub> etching using C <sub>4</sub> F <sub>6</sub> /O <sub>2</sub> /Ar plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2016, 34, .	0.9	6
148	Rapid electron density decay observed by surface-wave probe in afterglow of pulsed fluorocarbon-based plasma. Japanese Journal of Applied Physics, 2016, 55, 080309.	0.8	15
149	Thermal cyclic etching of silicon nitride using formation and desorption of ammonium fluorosilicate. Applied Physics Express, 2016, 9, 106201.	1.1	30
150	Non-thermal atmospheric pressure plasma activates lactate in Ringer's solution for anti-tumor effects. Scientific Reports, 2016, 6, 36282.	1.6	167
151	Synthesis of calcium oxalate crystals in culture medium irradiated with non-equilibrium atmospheric-pressure plasma. Applied Physics Express, 2016, 9, 096201.	1.1	10
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